



PHYSICAL AND ELECTRICAL CHARACTERIZATION OF
RF-SPUTTERED ITO FILMS FOR USE AS SOLAR CELL
ELECTRODES AS WELL AS INTERLAYERS IN LOW-
RESISTANCE MIS CONTACTS IN Ge/Si TRANSISTORS

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ENGR 241, Fall 2017



Contents

- Motivation
- Process Overview
- Design of Experiments (DOE)
- Repeatability Tests
- Final Results
- Summary

Contents

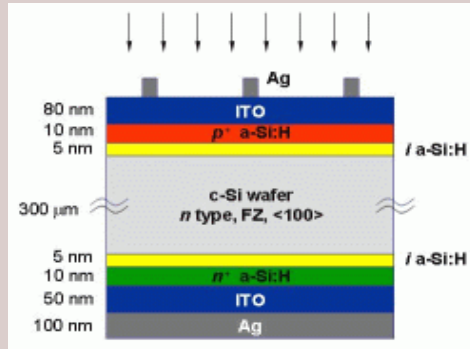
- **Motivation**
- Process Overview
- Design of Experiments (DOE)
- Repeatability Tests
- Final Results
- Summary
- Future Work

Motivation

Solar Application

Usage

Transparent Electrode



Thickness

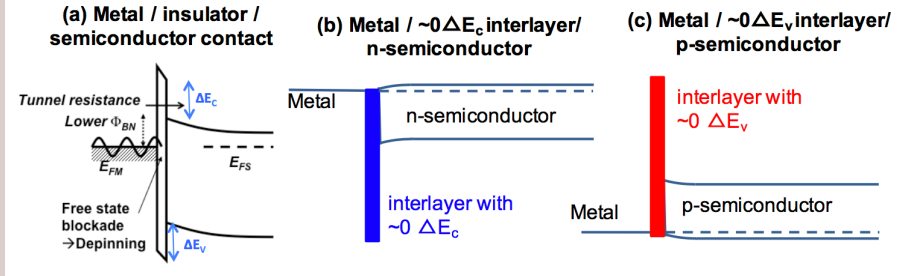
50-100 nm

Parameters to optimize

1. Maximum conductivity (Carrier Concentration)
 2. Maximum optical transmission over the solar spectrum (AM 1.5)
- Note:** These 2 objectives could oppose each other, i.e. more carriers (conductivity) will cause more absorption and thus decrease transmission.

MIS Contact Application

Interlayer in MIS contact



10-30 nm

Contents

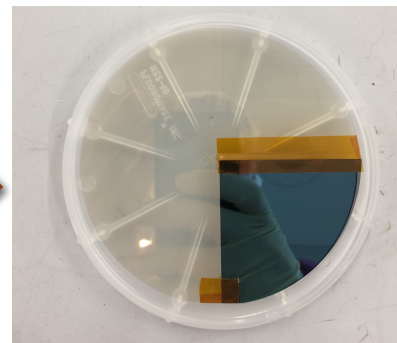
- Motivation
- **Process Overview**
- Design of Experiments (DOE)
- Repeatability Tests
- Final Results
- Summary
- Future Work

Process Overview - Sputtering

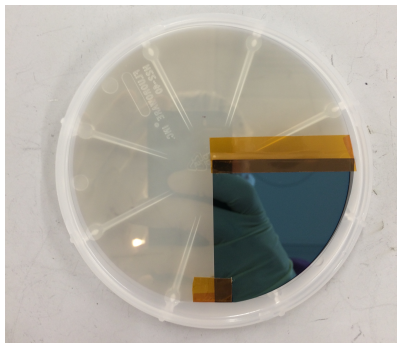


Glass Wafers +
Silicon Quarter
Wafers

Lesker Sputter
ITO Deposition



Process Overview - Measurements



- Thickness (Alphastep - profilometer)
- Sheet Resistance (Prometrix - 4-point probe)
- Transmission (Jasco - spectrophotometer)
- Stoichiometry (PHI V3 - XPS)
- Carrier Concentration (Hall Measurement tool in room 152 – Repeatability Issue)

Contents

- Motivation
- Process Overview
- **Design of Experiments (DOE)**
- Repeatability Tests
- Final Results
- Summary
- Future Work

Design of Experiments (DOE)

■ Factors

- › Pressure (3 mTorr – 5 mTorr)
- › Power (50 W – 100 W)
- › O₂/Ar Ratio (0 – 0.05)
- › Substrate Bias (0 – 50 V)
- › Temperature (Room Temperature – 270 °C)
 - Excluded from the initial screening
 - due to the complexities involved with the heating system

} 2⁴ = 16 Exp.



DOE



5 Exp.

8 Exp. to observe
3rd order
interactions


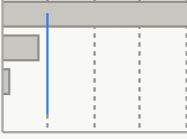
■ Responses

- › Resistivity (Minimize)/Carrier Concentration (Maximize)
- › Absorption Coefficient (Minimize)/Optical Transmission (Maximize)
 - Averaged over the solar spectrum (AM 1.5)

Design of Experiments (DOE) – Initial Results

Exp. #	Pressure (mTorr)	O ₂ /Ar Ratio	Power (W)	Subs. Bias (V)	Deposition Rate (nm/min)	Resistivity (ohm.cm)	Abs. Coeff. (1e4*cm ⁻¹)
1	5	0.05	100	50	0.82	8.67	6.57
2	5	0.05	50	50	0.43	7.48	7.42
3	5	0	100	0	2.50	2.3e-3	5.49
4	5	0	50	0	1.08	3.9e-3	6.57
5	3	0	100	0	1.78	7.2e-4	6.02
6	3	0	50	0	1.00	5.8e-4	4.98
7	3	0	100	50	1.53	4.8e-4	4.97
8	3	0	50	50	0.81	5.3e-4	5.49

Design of Experiments (DOE) - Analysis

Transmission				Resistivity			
Source	LogWorth		PValue	Source	LogWorth		PValue
O2/Ar ratio	0.542		0.28708	O2/Ar ratio	11.730		0.00000
Pressure	0.309		0.49038	Pressure	1.617		0.02416
Power	0.289		0.51444	Power	0.372		0.42457
Subs. Bias	0.145		0.71642	Subs. Bias	0.087		0.81845
Predicted Optimal Recipe							
Pressure (mTorr)	O ₂ /Ar Ratio	Power (W)	Subs. Bias (V)	Pressure (mTorr)	O ₂ /Ar Ratio	Power (W)	Subs. Bias (V)
3	0	100	50	3	0	100	50

- O₂/Ar ratio and then pressure have significant effects on resistivity values.
- High p-values in the transmission data
 - Semi-random distribution - no particularly significant factor
 - The predicted optimal recipe for transmission is not reliable.

Contents

- Motivation
- Process Overview
- Design of Experiments (DOE)
- **Repeatability Tests**
- Final Results
- Summary
- Future Work

Repeatability Tests

Exp. #	Pressure (mTorr)	O ₂ /Ar Ratio	Power (W)	Subs. Bias (V)	Resistivity (ohm.cm)		
					1 st Run	2 nd Run	3 rd Run
					Target 2	Target 1	Target 2
					Low Base Pressure	High Base Pressure	Low Base Pressure
2	5	0.05	50	50	7.48	13.2	N/A
4	5	0	50	0	3.9e-3	9.8e-03	3.52e-3
7	3	0	100	50	4.8e-4	1.75e-03	6.42e-4
8	3	0	50	50	5.3e-4	1.82e-03	8.45e-4

Resistivity data is repeatable

- Resistivity data is self-consistent through the 3 runs.
- High Base Pressure (and switch to target 1) increases the resistivity by a factor of ~2-4.

Repeatability Tests

Exp. #	Pressure (mTorr)	O ₂ /Ar Ratio	Power (W)	Subs. Bias (V)	Abs. Coefficient (1e4*cm ⁻¹)		
					1 st Run	2 nd Run	3 rd Run
					Target 2	Target 1	Target 2
					Low Base Pressure	High Base Pressure	Low Base Pressure
2	5	0.05	50	50	7.42	6.98	N/A
4	5	0	50	0	6.57	4.58	7.20
7	3	0	100	50	4.97	4.64	7.90
8	3	0	50	50	5.49	8.30	5.08

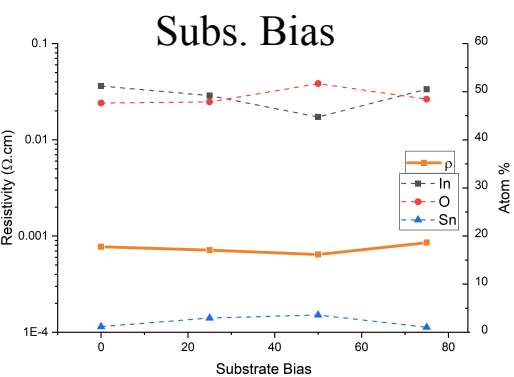
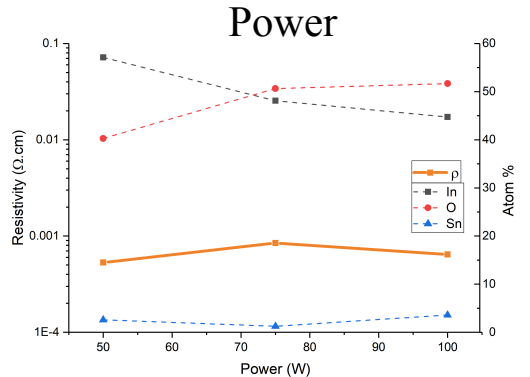
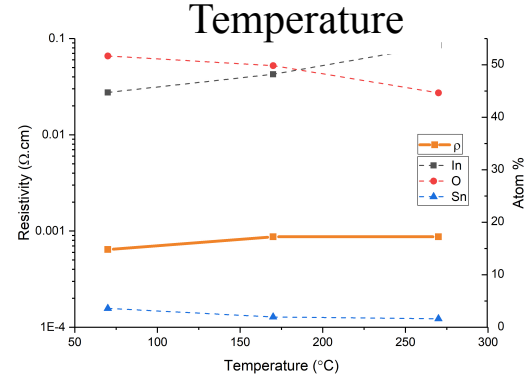
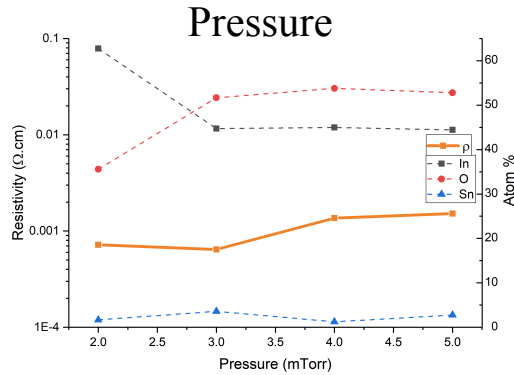
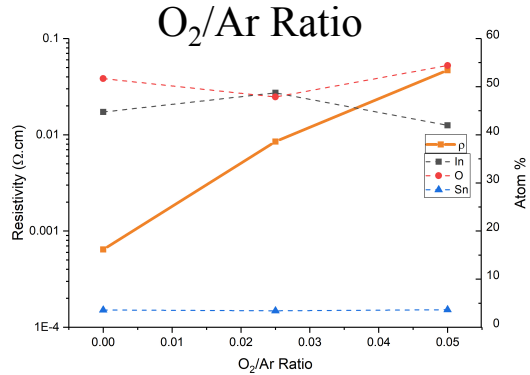
Transmission data is not completely repeatable

The reason is the semi-randomness nature of the transmission data, as verified by the high p-values.

Contents

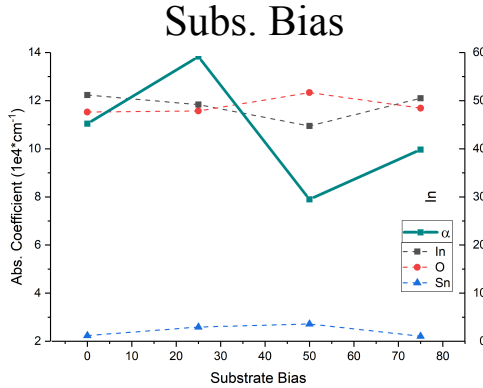
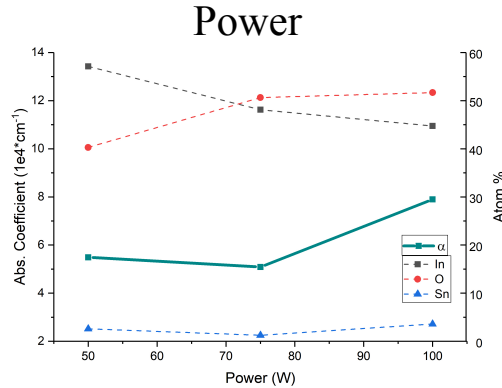
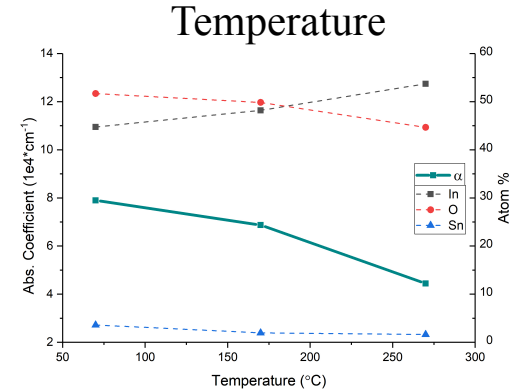
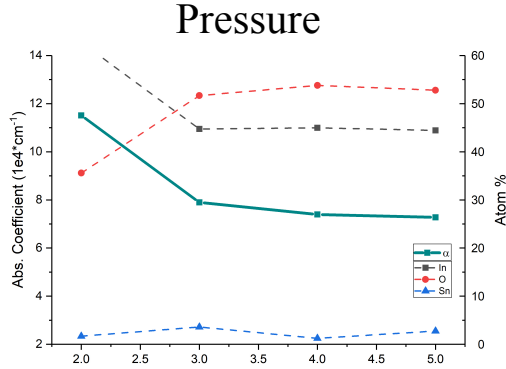
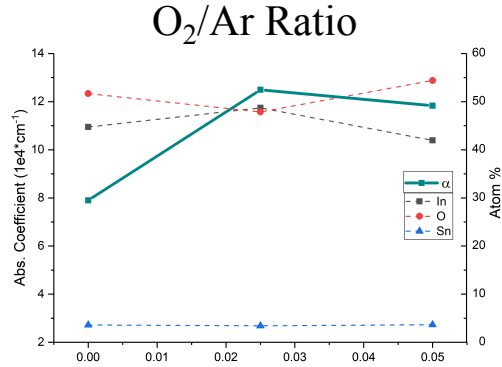
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Final Results – Resistivity Trends



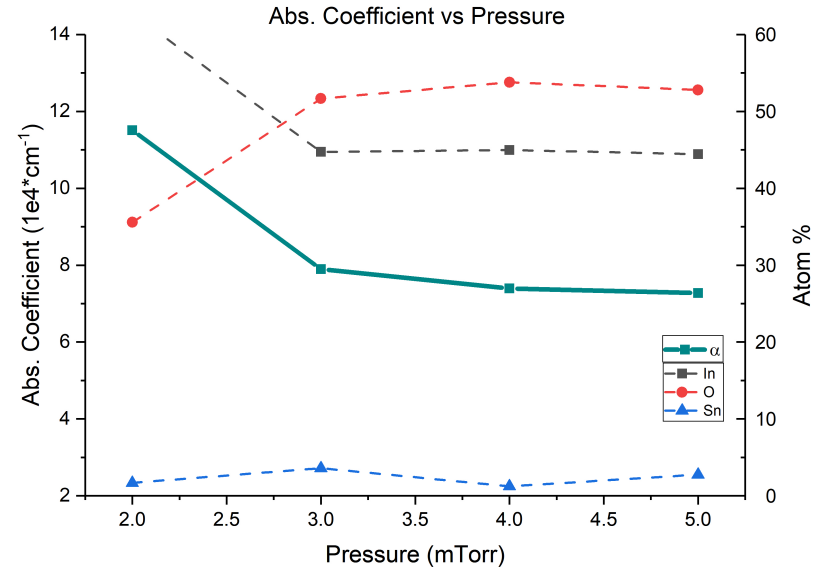
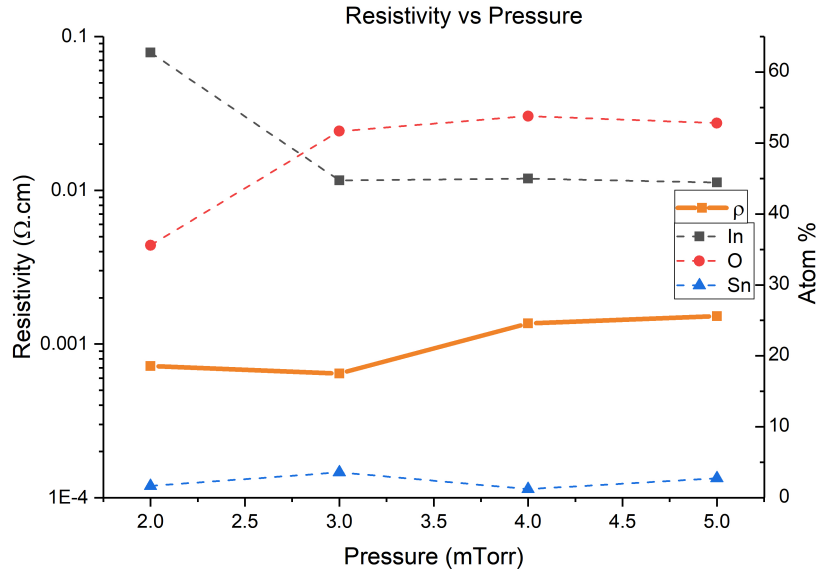
Optimal Resistivity Recipe	
O ₂ /Ar Ratio	0
Pressure	3 mTorr
Power	100 W
Subs. Bias	50 V
Temperature	~ 70 °C
Resistivity	4.8e-4 ohm.cm

Final Results – Transmission Trends



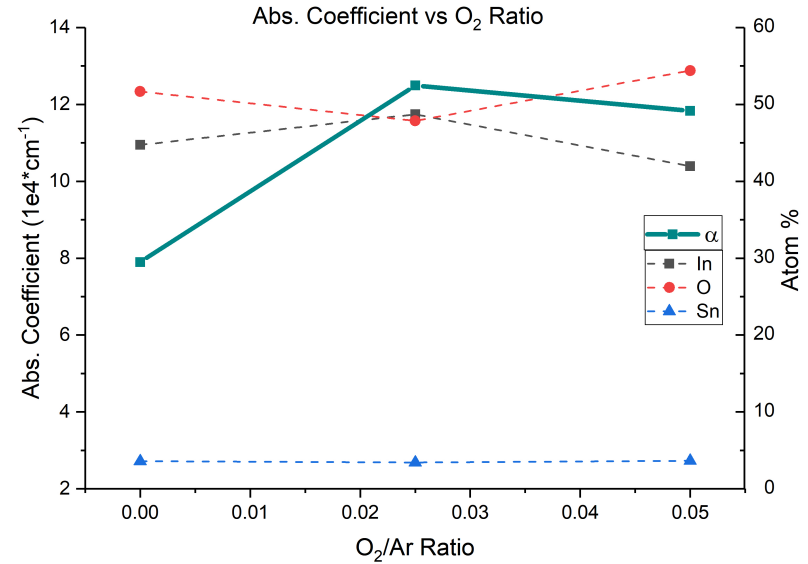
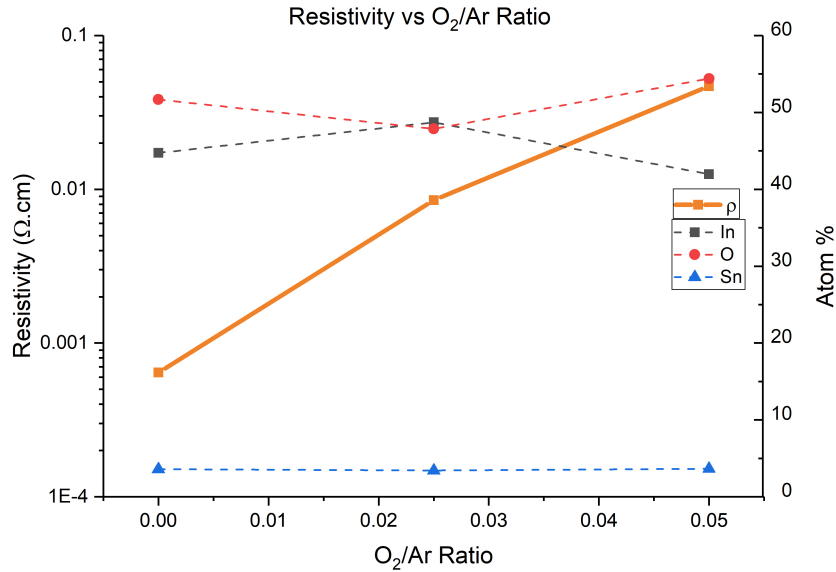
Optimal Transmission Recipe	
O ₂ /Ar Ratio	0
Pressure	3 mTorr
Power	100 W
Subs. Bias	50 V
Temperature	270 °C
Abs. Coeff.	44400 cm ⁻¹

Final Results - Effect of Pressure



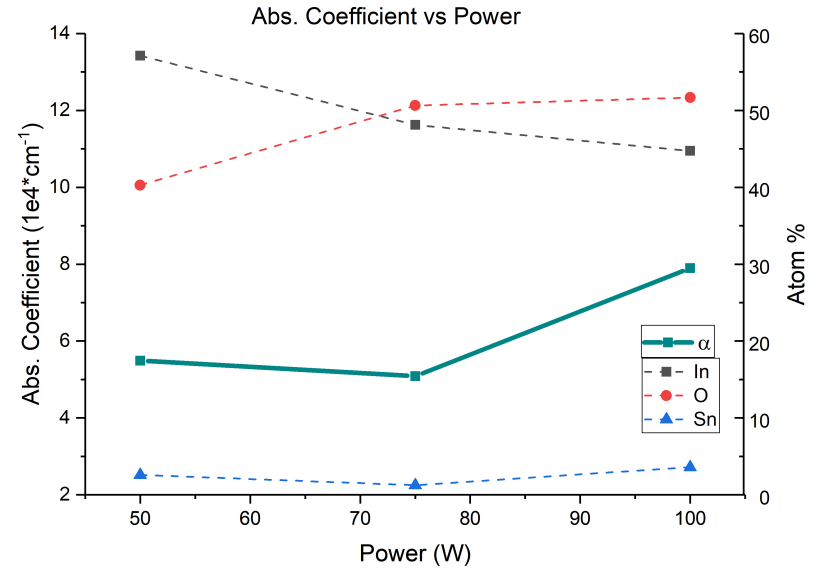
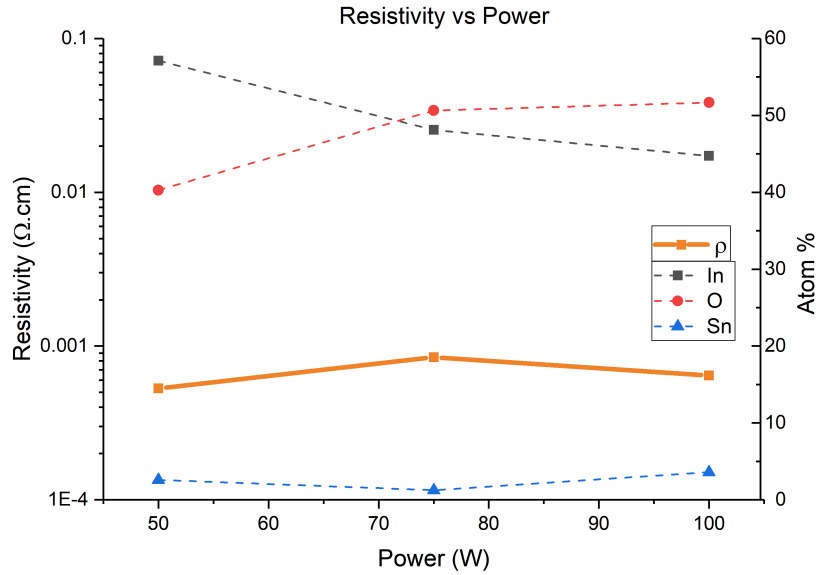
More Sn (Tin) → More conductivity
More Oxygen → More Transmission

Final Results - Effect of O₂/Ar Ratio



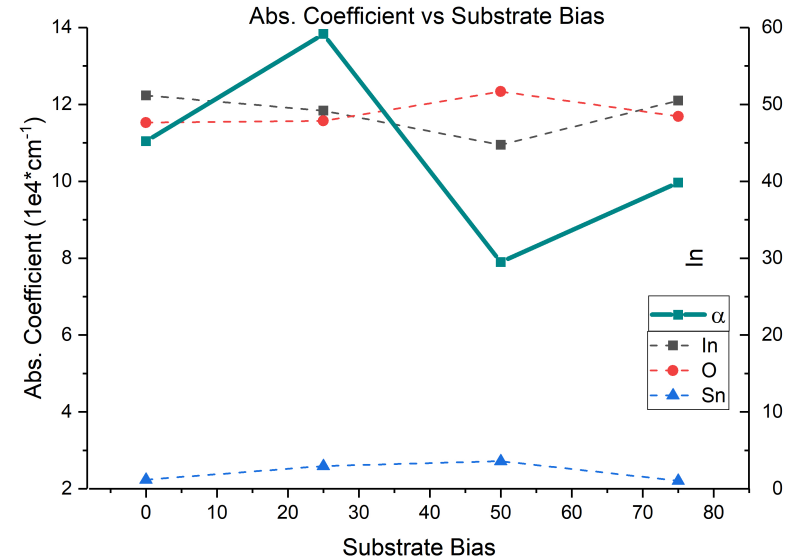
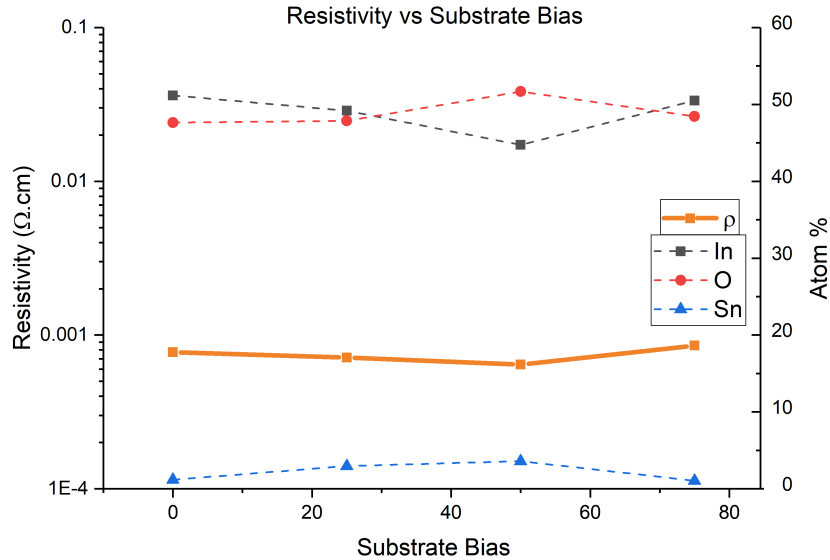
More Sn (Tin) → More conductivity
More Oxygen → More Transmission

Final Results - Effect of Power



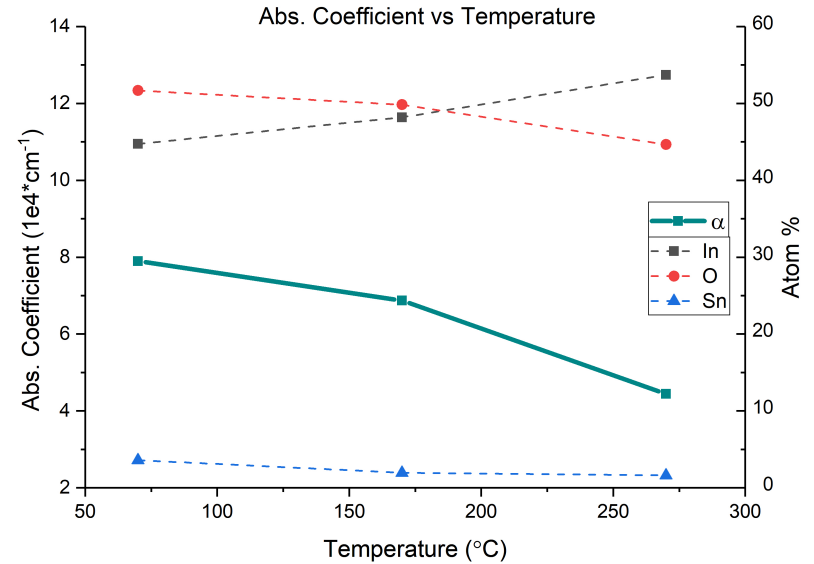
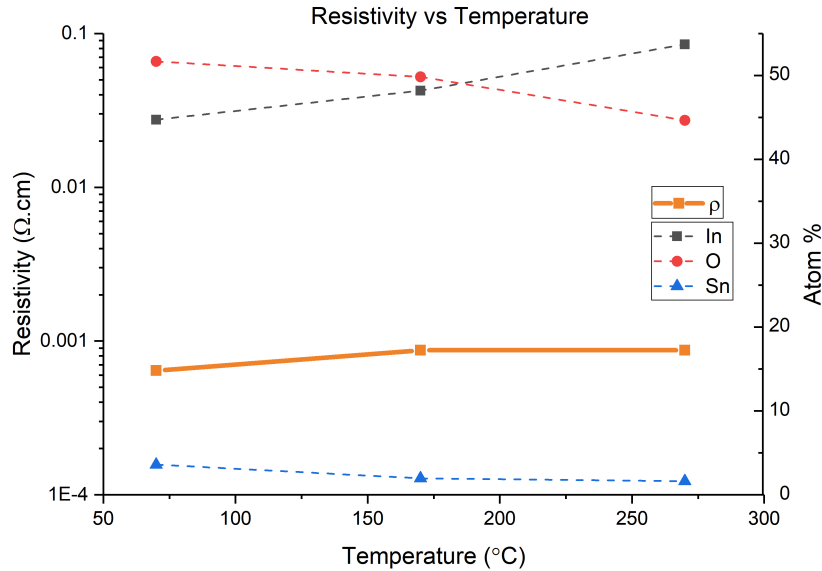
More Sn (Tin) \rightarrow More conductivity
More Oxygen \rightarrow More Transmission

Final Results - Effect of Substrate Bias



More Sn (Tin) → More conductivity
More Oxygen → More Transmission

Final Results - Effect of Temperature



More Sn (Tin) \rightarrow More conductivity
Less Oxygen \rightarrow More Transmission

- Effect of Annealing

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Summary

- Optimal Recipes

Optimal Resistivity Recipe	
O ₂ /Ar Ratio	0
Pressure	3 mTorr
Power	100 W
Subs. Bias	50 V
Temperature	~ 70 °C
Resistivity	4.8e-4 ohm.cm

Optimal Transmission Recipe	
O ₂ /Ar Ratio	0
Pressure	3 mTorr
Power	100 W
Subs. Bias	50 V
Temperature	270 °C
Abs. Coeff.	44400 cm ⁻¹

- More Sn → More conductivity
- More Oxygen → More Transmission
- More Annealing (Heating) → More transmission

Contents

- Motivation
- Process Overview
- Design of Experiments (DOE)
- Repeatability Tests
- Final Results
- Summary
- **Future Work**

Future Work



- Accurate Hall Measurements done at INTERMOLECULAR®
 - › Thanks to Vijay Narasimhan
- Fabricating MIS contacts using our optimal resistivity recipe
 - › Done by Pranav Ramesh

Acknowledgement

- SNF Staff
- E 241 Class
- Our mentors
 - › Maurice Stevens
 - › Vijay Narasimhan
 - › Pranav Ramesh

Q & A

Thank you!

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